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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/040,272	11/07/2001	Paul Janis Timans	AGX-45-CIP	AGX-45-CIP 9676		
22827 75	590 11/16/2004		EXAM	EXAMINER		
DORITY & MANNING, P.A. POST OFFICE BOX 1449			FUQUA, SHA	FUQUA, SHAWNTINA T		
	SC 29602-1449		ART UNIT	PAPER NUMBER		
			3742			
			DATE MAIL ED: 11/16/2004	•		

Please find below and/or attached an Office communication concerning this application or proceeding.

					MAA			
Office Action Summary		Applicatio	n No.	Applicant(s)	<u> </u>			
		10/040,27	2	TIMANS, PAUL J	ANIS			
		Examiner		Art Unit				
		Shawntina		3742				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply								
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).  - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).  Status								
1)🖂	Responsive to communication(s) filed on <u>01 Ju</u>	uly 2004.						
2a) <u></u> □	This action is <b>FINAL</b> . 2b)⊠ This a	action is no	n-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposition of Claims								
4)🖂	Claim(s) <u>1-12,14-35,37-78 and 82-139</u> is/are p	ending in th	e application.					
4a) Of the above claim(s) 16-26 and 37-52 is/are withdrawn from consideration.								
5)⊠ Claim(s) <u>1-12,14,15,27-35,53-78 and 92-102</u> is/are allowed.								
· · · · · · · · · · · · · · · · · · ·	6)⊠ Claim(s) <u>82-91 and 103-139</u> is/are rejected.							
·	Claim(s) is/are objected to.	r alaatian ra	au irom ont					
8) Claim(s) are subject to restriction and/or election requirement.								
Application Papers								
9) The specification is objected to by the Examiner.								
10)⊠ The drawing(s) filed on <u>07 November 2001</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.								
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).								
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.								
Priority under 35 U.S.C. §§ 119 and 120								
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).								
a) ☐ All b) ☐ Some * c) ☐ None of:								
1. Certified copies of the priority documents have been received.								
<ul> <li>2. Certified copies of the priority documents have been received in Application No.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage</li> </ul>								
application from the International Bureau (PCT Rule 17.2(a)).								
* See the attached detailed Office action for a list of the certified copies not received.  13) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application)								
since a specific reference was included in the first sentence of the specification or in an Application Data Sheet. 37 CFR 1.78.								
a) The translation of the foreign language provisional application has been received.								
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121 since a specific reference was included in the first sentence of the specification or in an Application Data Sheet. 37 CFR 1.78.								
Attachmen	t(s)		•					
2) Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s) <u>8/</u>		4) Interview Summary ( 5) Notice of Informal Pa 6) Other:					

#### **DETAILED ACTION**

### Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 82-91, and 103-139 are rejected under 35 U.S.C. 103(a) as being unpatentable over Dobson et al (US4959245) in view of Griner et al (US4780590) and Tanaka (US6693257).

Dobson et al discloses a process for heating semiconductor substrates comprising placing a substrate in a processing chamber (column 3, lines 30, 35-38), directing light energy (9) onto substrate at an angle of incidence greater than 0, 10, 40-85 degrees (column 5, lines11-23) wherein the light energy contacts the substrate in a p-polarized plane (column 4, lines 7-23), wherein substrate is heated by light energy in combination with other energy sources such as light energy sources (column 6, lines 27-40), light energy source is a pulsed laser beam (9, column 5, lines 11-15) which strikes the substrate to carry out an ion implantation anneal process (column 5, lines 32-34). Dobson et al does not disclose redirecting light energy that is reflected off the substrate onto the substrate, scanning the laser beam over the surface of the substrate, an electrical resistance heater, a laser diode, and a silicon wafer. Griner et al discloses redirecting light energy that is reflected off the substrate onto the substrate (column 9, lines 57-63), scanning the laser beam over the surface of the substrate (abstract), and Tanaka discloses a laser diode (column 5, lines 10-14, 32-43) and a silicon wafer (column 13, lines 54-66). It would have been

Application/Control Number: 10/040,272 Page 3

Art Unit: 3742

obvious to one of ordinary skill in the art at the time the invention was made to have included the light energy control aspect, and scanning of Griner et al along with the laser diode and silicon wafer of Tanaka in the process of Dobson et al because, changing the configuration of light energy to change the amount of light absorbed by the substrate, redirecting light energy that is reflected off the substrate onto the substrate, scanning the laser beam over the surface of the substrate, and using a laser diode allows the substrate temperature to be controlled more accurately.

In addition, while neither Dobson et al or Griner et al discloses an electric resistance heater, Dobson et al does disclose a substrate heater in contact with the sample via the support stage. This disclosure suggests that the substrate support is heated and is acting as a heated plate. A heating plate with an electric resistance heater is conventional and well known. It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included an electric resistance heater in the substrate support as a means to heat the substrate more uniformly.

## Allowable Subject Matter

3. Claims 1-12, 14-15, 27-35, 53-78, and 92-102 are allowed.

## Response to Arguments

4. Applicant's arguments with respect to claim have been considered but are moot in view of the new ground(s) of rejection.

#### Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shawntina T. Fuqua whose telephone number is (703) 305-2581. The examiner can normally be reached on Monday-Friday 8-4:30 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robin Evans can be reached on (703) 305-5766. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

stf

November 15, 2004

Shawntina Fuqua
Patent Examiner

Art Unit 3742